



[ThA2] Nanoscale Thin Film Deposition VII

Session Date	November 13 (Thu.), 2025
Session Time	10:50–12:00
Session Room	Room A (Capri Room, 2F)
Session Chair	Prof. Changhwan Choi (Hanyang Univ., Korea)

[ThA2-1] [Invited]

10:50–11:20

Atomic Layer Deposition Process Development of Molybdenum Dioxide for the DRAM Capacitor Electrode Applications

Chaeyeong Hwang, Soo Min Yoo, and Woojin Jeon (Kyung Hee Univ., Korea)

[ThA2-2] [Invited]

11:20–11:40

Optimization of Atomic Layer Deposition Chemistry Toward Advanced Semiconductor Applications

Woo-Jae Lee (Pukyong Nat'l Univ., Korea)

[ThA2-3]

11:40–12:00

Improved Thermal Stability and Retention in Carbon-Doped $\text{Ge}_2\text{Sb}_2\text{Te}_5$ -Based Phase-Change Random Access Memory

Jisu Park, Wooseong Son, Seung Min Kang, and Changhwan Choi (Hanyang Univ., Korea)